



Workshop on Diffraction Limited Storage Rings

9-11 December, 2013

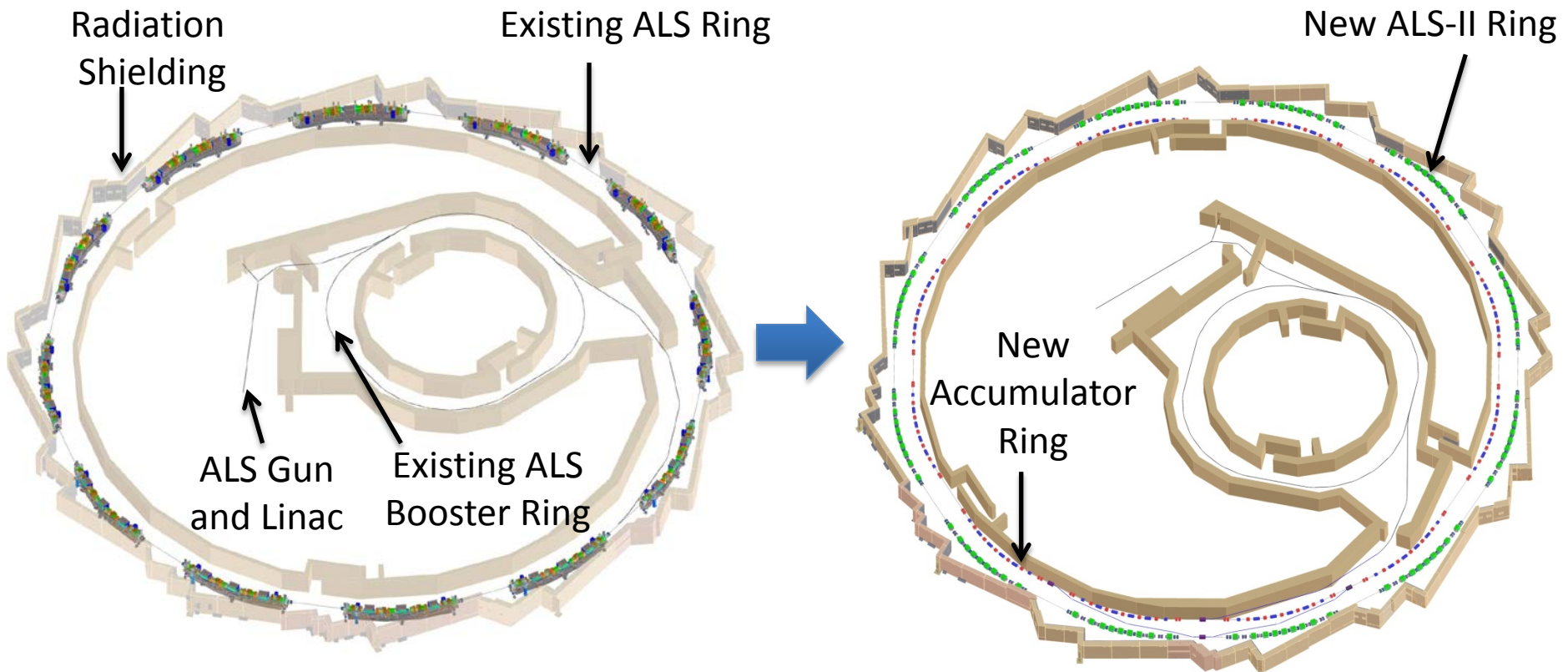
SLAC National Accelerator Laboratory, Menlo Park, CA

ALS-II Vacuum system and NEG coating

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From ALS to ALS-II



- New high performance storage ring based on multi-bend achromat (9 bends per arc) in same building and tunnel
- Same circumference (197 m), straight section length, location and symmetry

Why Distributed Ti-Zr-V NEG Technology?

- ❑ Research and development underway since early 1990's: first at CERN, later also at other places, incl. commercial developments, incl. SAES
- ❑ Proven technology for achieving UHV in chambers with small cross sections: Matured technology used at ESRF and SOLEIL; more work is underway at BESSY and NSLS-II, and at other light sources.
- ❑ a section of ~ 2 m length has ~300 l/s pumping speed at pressures < 10^{-9} Torr
- ❑ this pumping rate compares favorably with existing antechamber structures; allowing small gap designs.
- ❑ Typical activation range 180°C for 24 h, or 200°C for 1 h, which is compatible with designs and procedures for synchrotrons

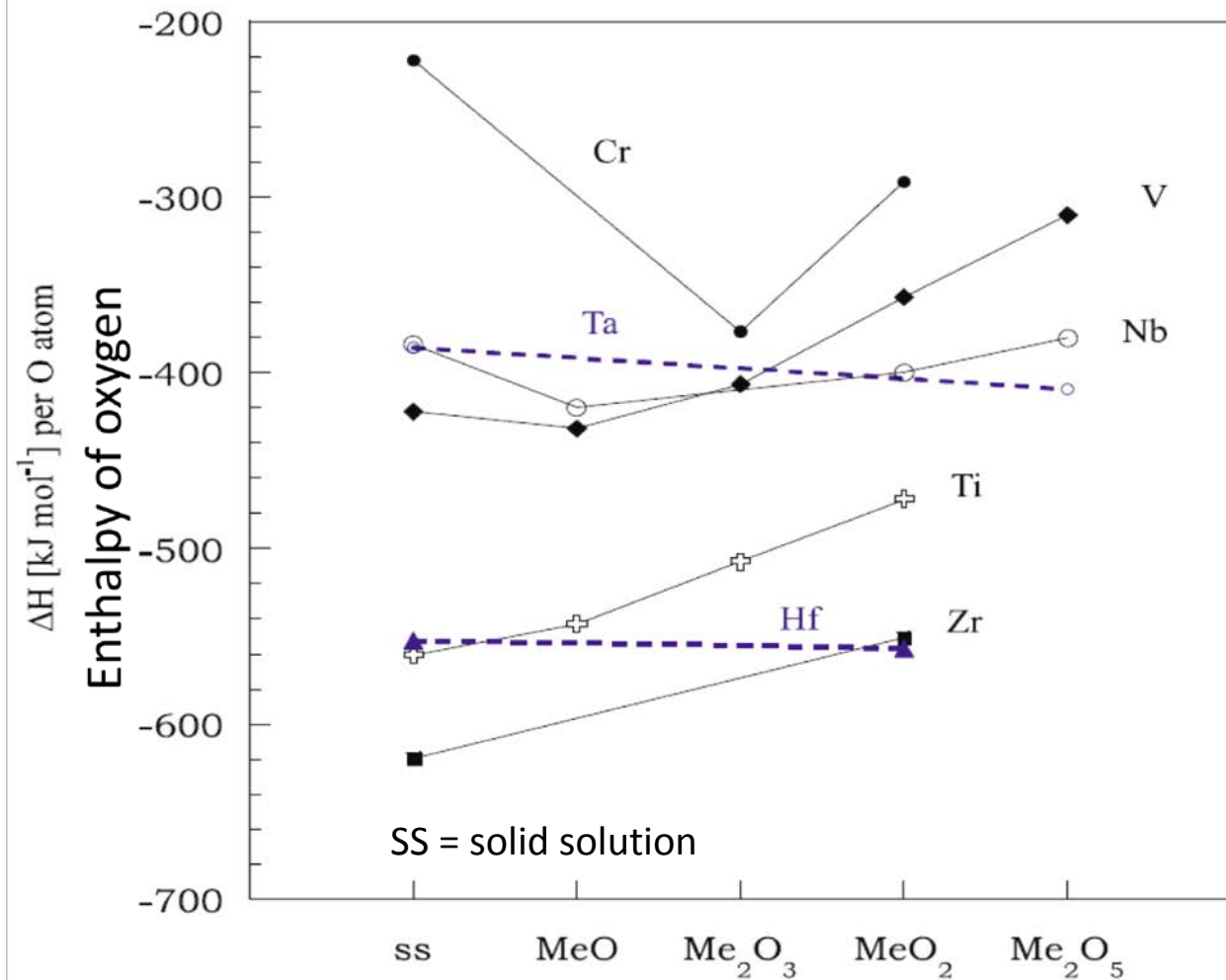
Reminder: NEG – how does it work?

thermodynamic considerations

- oxygen from the surface diffuses into bulk because this lowers the free energy of the system: Free energy of oxygen in SS must be smaller than free energy of oxide
- solubility increases in the presence of grain boundaries

kinetic considerations

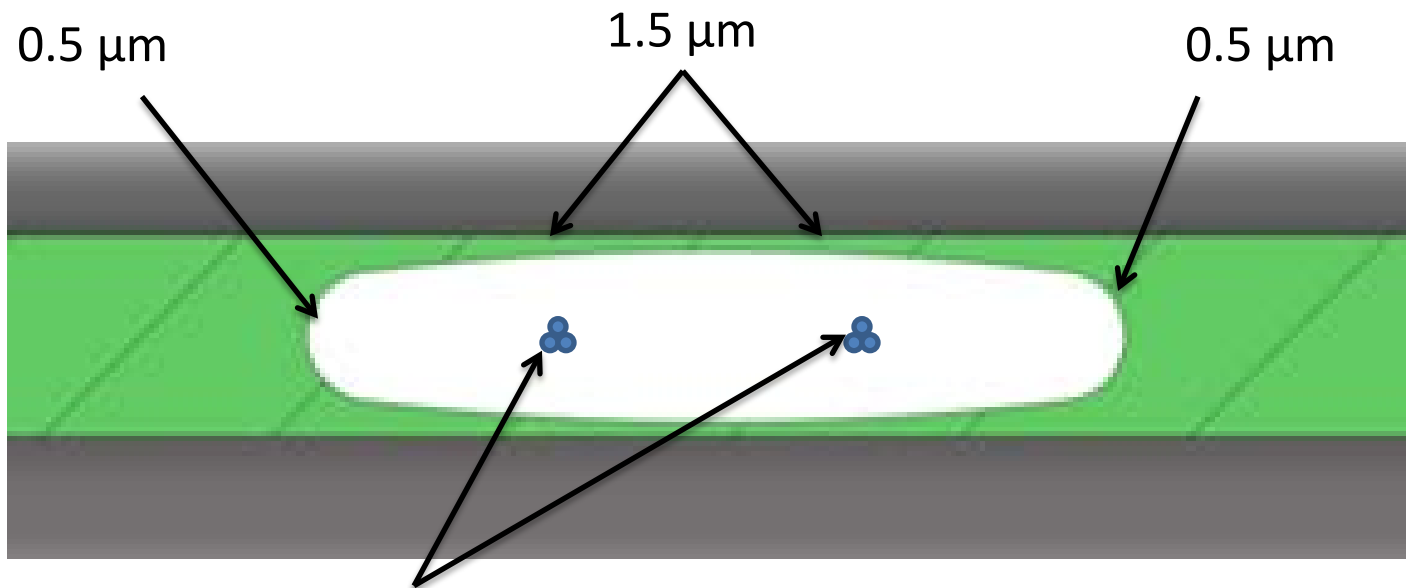
- oxygen diffusivity increases with temperature
- solubility increases with temperature
- concentration gradient needs to be sufficiently high for diffusion to occur



“activation” of the Ti-Zr-V (Hf) coatings at about 180°C

NEG Coating Process (SAES)

- Magnetron sputtering process inside vertical chamber
- Room temperature process
- Coating thickness = $1\ \mu\text{m}$ ($\pm 0.5\ \mu\text{m}$)



Ti-Zr-V Cathodes are formed by a wire triplets.
Wire Diameter $\sim 1\ \text{mm}$.

Two
Vertical
Ti-Zr-V
Cathodes

2.3 m

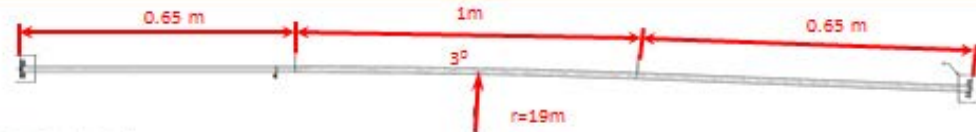
0.3 m (2X)

NEG coating inside long straight vs. curved chambers

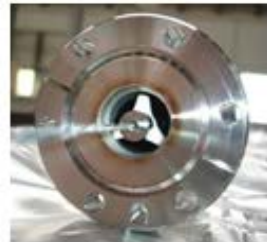


NEG coating: R&D at CERN

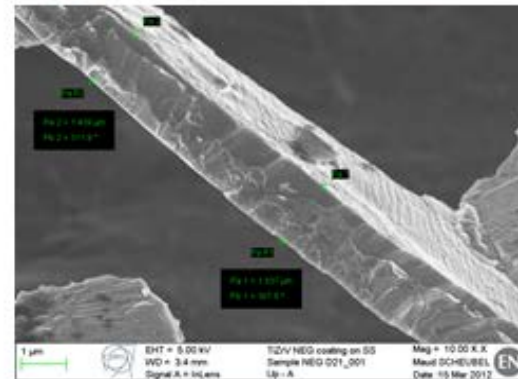
Bent VC:



Ceramic spacers fixed with two Titanium discs



Coating clearly visible on ceramic spacers



Coating thickness

Challenges

The challenges are:

- to make NEG coatings in very small (< 10 mm) aperture, high length/diameter ratio (200-500) vacuum chambers.
- to integrate ports for many beamlines into the small aperture vacuum system, implying many aperture changes and changes of the width/height ratio where the photon beamlines leave the main chamber

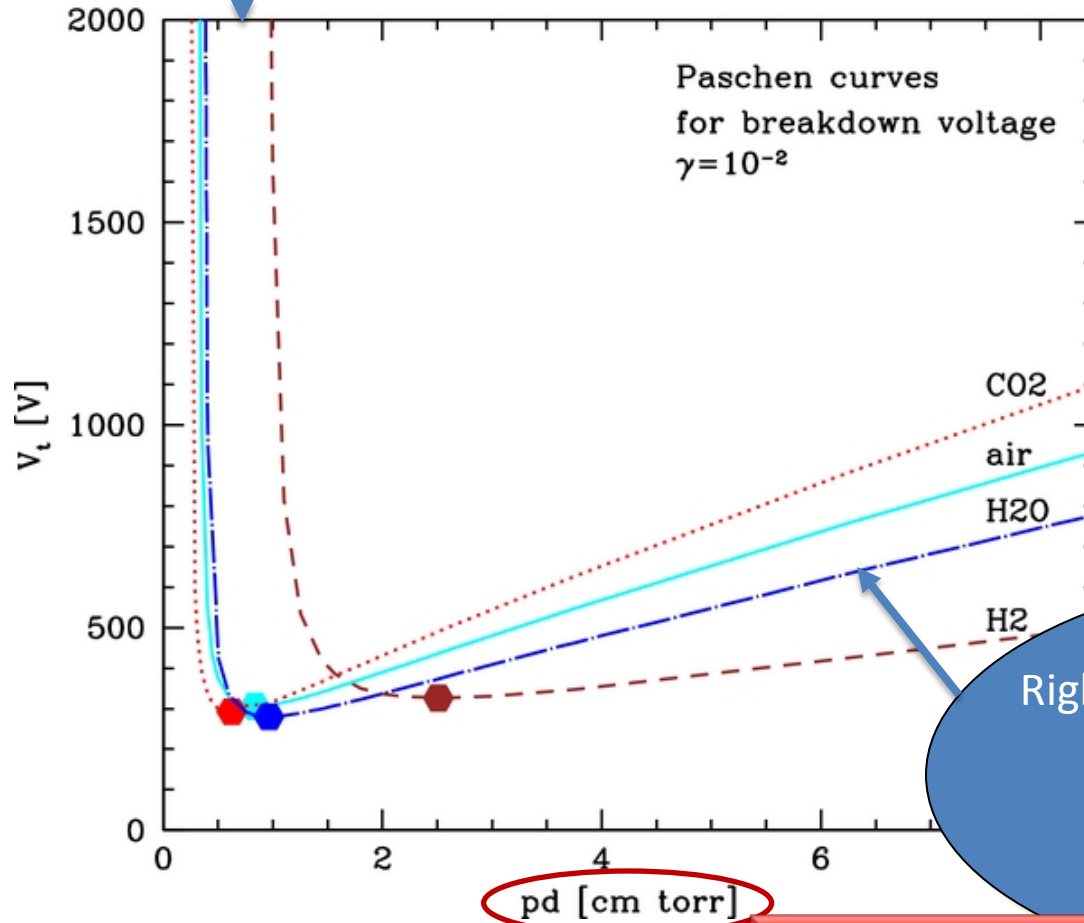
Options regarding the coating include:

- scaling of the established process
- inventing new processes

Paschen Curves



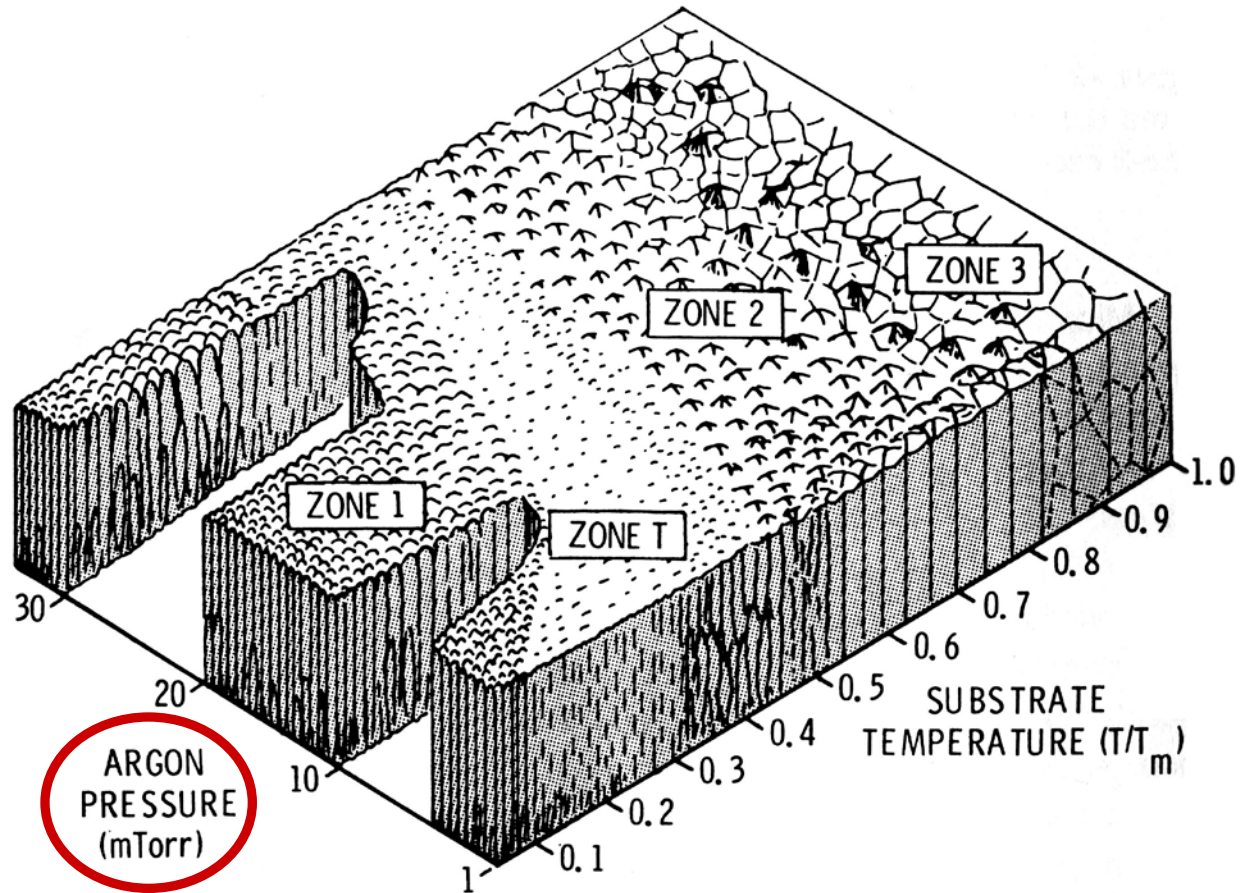
Louis Karl Heinrich
Friedrich Paschen
(1865 - 1947)



Right side of the curve's minimum:
Many collisions prevent
electron energy gain:
mean free path $\ll d$

pd contains the scaling with pressure!

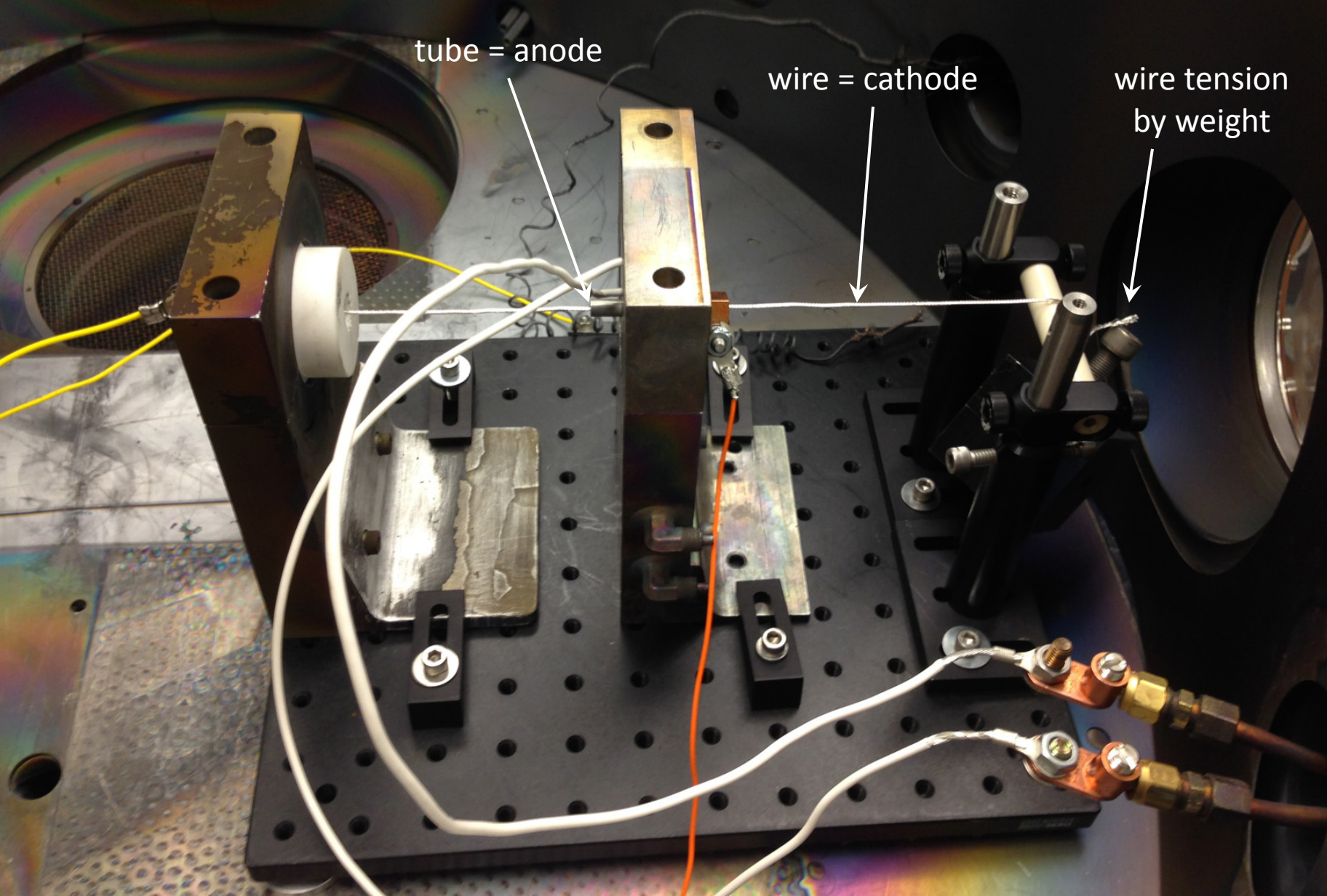
Thornton's Structure Zone Diagram of Film Microstructure for Sputtering



Contains the effects of energetic particle bombardment, and more precisely, it should be pd

Very First Setup:

Goal to demonstrate plasma in a 4 mm inner diameter tube at rel. high pressure



tube = anode

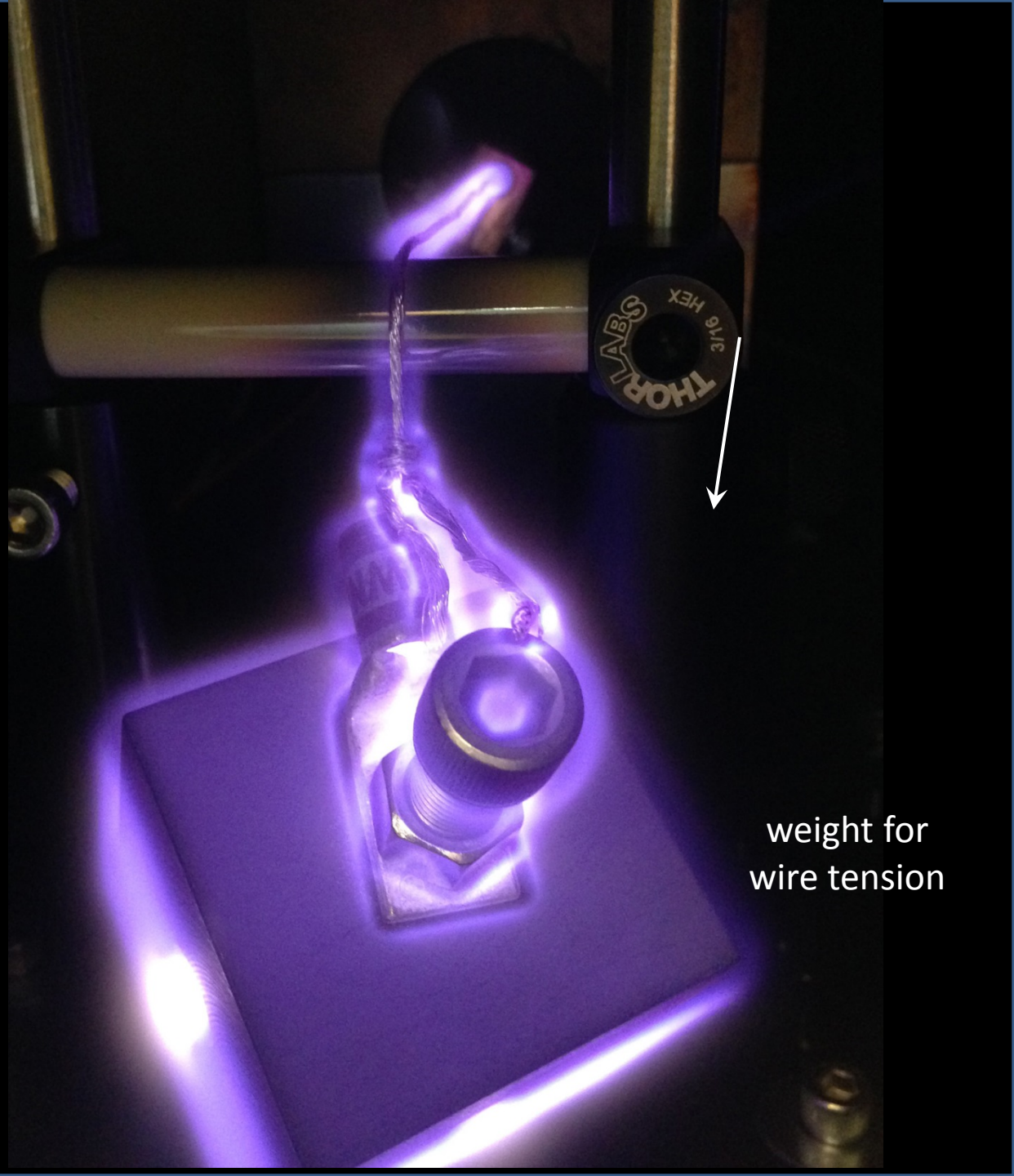
wire = cathode

wire tension
by weight

Glow Discharge at 4 Torr



negative glow
plasma has a
scale ~ mm



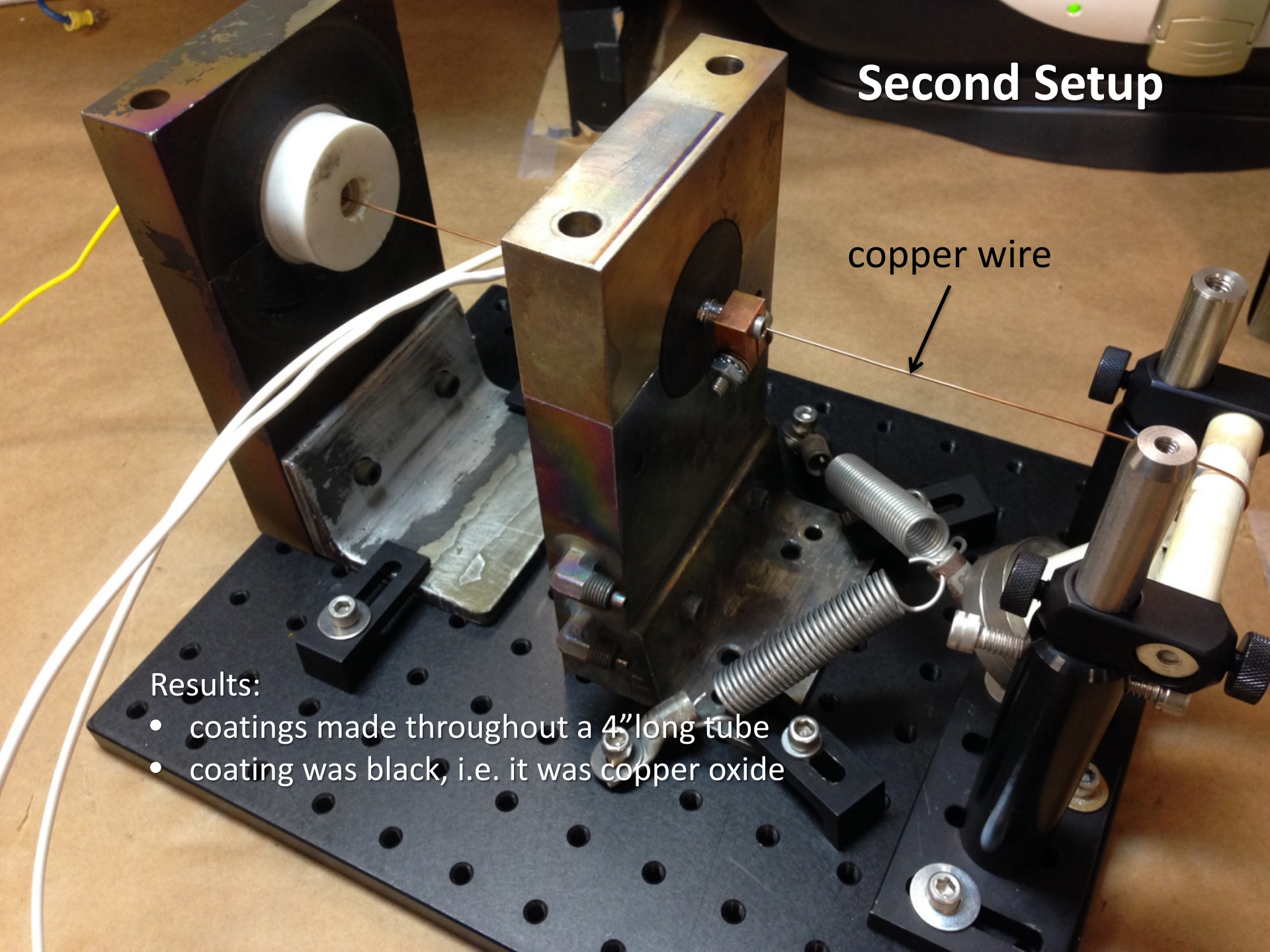
weight for
wire tension

Second Setup

copper wire

Results:

- coatings made throughout a 4" long tube
- coating was black, i.e. it was copper oxide



Summary of Preliminary Results & Outlook

- ALS-II vacuum system has the same length as original synchrotron (~ 200 m) but significantly smaller chambers: preliminary design calls for straight sections that have inner diameter down to 4 mm, and varying cross sections and aspect ratios at beamlines
- 10^{-10} Torr range is required \rightarrow NEG (Ti-V-Zr) coating is needed
- NEG with low activation temperature is highly desirable (e.g. 180°C)
- Challenges
 - to scale the deposition technology to very small apertures
 - to deal with varying cross sections and aspect ratios
- Approach:
 - either scale the proven central-wire-cathode-based sputtering method, or
 - invent alternate options: none of the ideas have been tested yet
- Preliminary, crude experiments showed that plasma can be made in relatively short, 4 mm inner diameter tubes, and coating can be produced, yet much remains to be solved.